



SUPPLEMENTAL INFORMATION CITED BY APPLICANT THAT MAY BE MATERIAL
TO THE PROSECUTION OF THE SUBJECT APPLICATION

Applicant: N.B. Cobb Attorney Docket No. MEGC121783
Application No.: 10/696,276 Group Art Unit: 2123/Confirmation No. 6511
Filed: October 29, 2003 Examiner: J.C. Ochoa
Title: METHOD AND APPARATUS FOR PERFORMING OPC USING MODEL
CURVATURE

U.S. PATENT DOCUMENTS

None

FOREIGN PATENT DOCUMENTS

None

OTHER INFORMATION

(Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Cite
Initial No.

already considered
JO O3 Previously submitted on 2/5/04 and enclosed for Examiner's convenience:
Cobb, N., et al., "Mathematical and CAD Framework for Proximity
Correction," *Proceedings of the International Society for Optical Engineering*
2726: 208-222, 1996.

JO O12 Previously submitted on 2/5/04 and enclosed for Examiner's convenience:
Vacca, A., et al., "Techniques to detect and analyze photomask CD uniformity
errors," *Proceedings of SPIE, 19th Annual Symposium on Photomask
Technology, Paper 3873-21*, Pages 209-214, 1999.

Examiner

Date Considered

*Examiner: Initial if reference considered, whether or not citation is in conformance with
M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include
copy of this form with next communication to applicant.

RCT:pt

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